

研究開発用実験炉 製品ガイド

High-temperature vacuum furnace

【カーボン炉、タングステン炉】(内熱式)

1inch

2inch

3inch

4inch

6inch

8inch

手動制御

Mini-BENCH



Max 2000C

CCC heater element
Vacuum or Inert Gas

- A) Chamber
- B) Temperature Controller/PSU
- C) Vacuum equipments (Pump, valves & Gauge)

*A + B is minimum configuration. C is also acceptable if requested.

セミオート PLC 自動シーケンス

Mini-BENCH-prism



Max 2000C

CCC heater element
Vacuum or Inert Gas

- 7inch Touch panel HMI
- PLC auto sequence: Pump/purge cycle & Vent
- Pump/gauge, DC PSU are all stored in cabinet
- Plug and play
- Lid open/close: momentary switch
- Safety option:
 - Water flow meter
 - Chamber thermostat
 - Pop off valve
 - EMO

Compact footprint: 603 (W) x 603 (D) x 1171 (H) mm

MiniLab-CF, -WCF



Max 2900C (CF)

Max 2000C (WCF)

【SiC, TiC コーティングヒーター マルチ雰囲気炉】(内熱式)

1inch

2inch

3inch

4inch

6inch

8inch

セミオート PLC 自動シーケンス

Thermic Edge furnace_TE



Max 2000C

Heater option:
*SiC3 coating
*TiC3 coating

- 7" Touch panel
- PLC auto sequence
- Plug and play
- Safety option:
 - Water flow
 - Chamber thermostat
 - Pop off valve
 - EMO

Compact Bench-top size:
889 (W) x 503 (D) x 629 (H) mm *exclude pump

MiniLab-CF (Max 2000C), -WCF (Max 2000C)



Max 2000C

- *SiC3 coating or TiC3 coating heater option
- max 8inch wafer annealing
- 2900C furnace: C thermocouple & Pyrometer
- PLC auto sequence, Plug and play

1240 (W) x 535 (D) x 1667 (H) mm *exclude pump

研究開発用実験炉 製品ガイド

High-temperature vacuum furnace

【石英反応管縦型炉】（外熱式）

1inch

2inch

3inch

4inch

6inch

8inch

手動制御

TVF-110, Vertical furnace



Max 1200C

Quartz reactor, clean wafer annealing
Vacuum or Processing gases

Heater: Kanthal element
Wafer size: 1~4inchr
K type thermocouple

Quartz wafer susceptor
Manual load, manual z-shift lift up

【石英反応管（横型）】 ホットウォール式 熱 CVD（外熱式）

1inch

2inch

3inch

4inch

6inch

8inch

手動制御（APC 圧力コントロール）

Nanofurnace, Model. BWS-NANO

for Carbon Nanotube, Graphene synthesis, ZnO nanowires.



Max 1200C

Hot wall type T-CVD
3 x MFC: CH₄, Ar, H₂
1 x MFC for bubbler

APC pressure control with precise capacitance manometer
Rotary Pump
'Lab View' software

研究開発用実験炉 製品ガイド

High-temperature vacuum furnace

【ウエハーアニール装置 (カスタムメイド真空チャンバー)】 (内熱式)

1inch

2inch

3inch

4inch

6inch

8inch

手動制御

Custom made chamber with substrate heater

Customer made vacuum chamber, Substrate Heater, vacuum equipments.



Φ4inch_1200C, SiC coated heater



Vacuum chamber, front view port

We provide bespoke solutions for annealing system, heating applications that cannot be fulfilled using standard products. These systems, heaters can be any shape to suit your application.

【ウエハーアニール装置 セミオート制御, APC 圧力コントロール】 (内熱式)

1inch

2inch

3inch

4inch

6inch

8inch

セミオート PLC 自動シーケンス (APC 圧力コントロール)

ANNEAL by Moorfield



Max 1000C

3 types of heating element options;

- Halogen lamp heater (600C)
- CCC heater (1000C)
- SiC coated CCC (1000C)

7inch Touch panel HMI

PLC auto sequence: Pump & Vent cycle

3 x MFC' s
Precise pressure control
Capacitance manometer, high-resolution pressure control

Wafer size: 4inch and 6inch
K type thermocouple
Turbo Pump with RP (or Dry scroll) backing pump